Electronic Supplementary Material (ESI) for RSC Advances.

Two-step deposition of Ag nanowires/Zn_2SnO_4 transparent conductive electrodes for antistatic coatings

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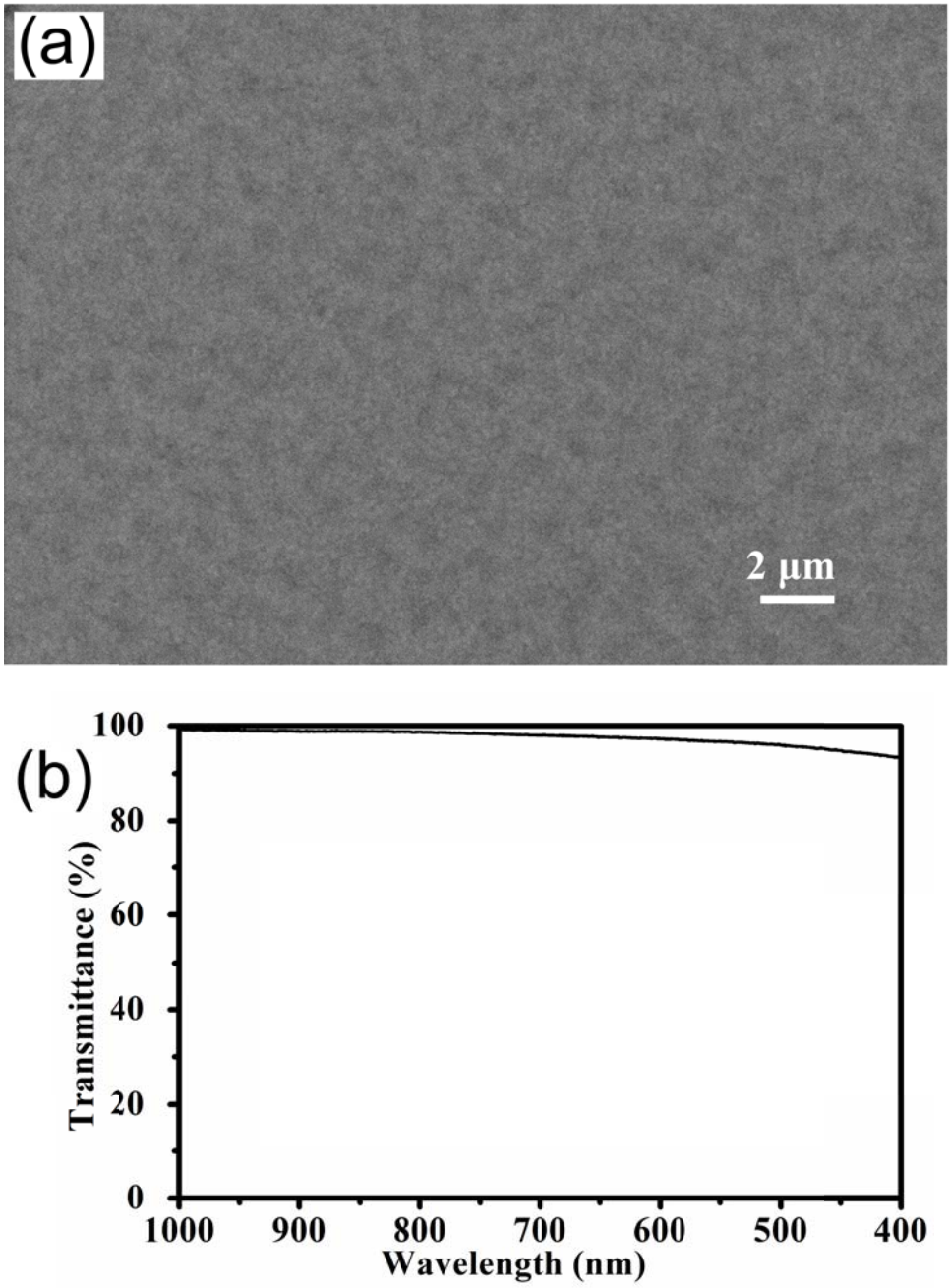

Fig. S1. SEM image (a) and transmission spectrum (b) of a pure Zn_2SnO_4 film.

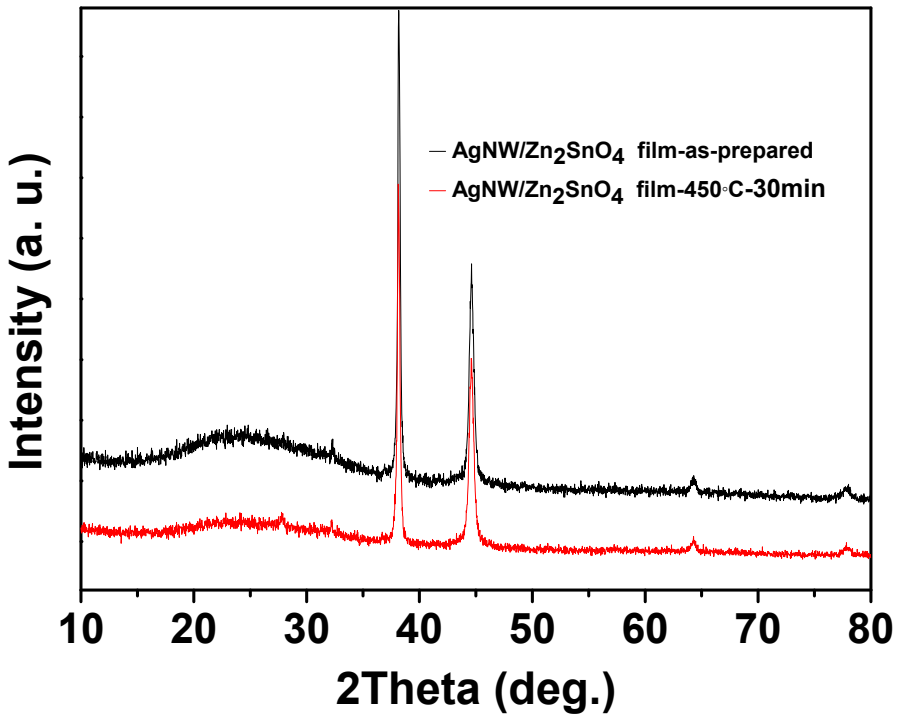

Fig. S2. XRD patterns of as-prepared AgNW/Zn_2SnO_4 composite thin film and the corresponding thin film annealed at 450^{o}C for 30min.

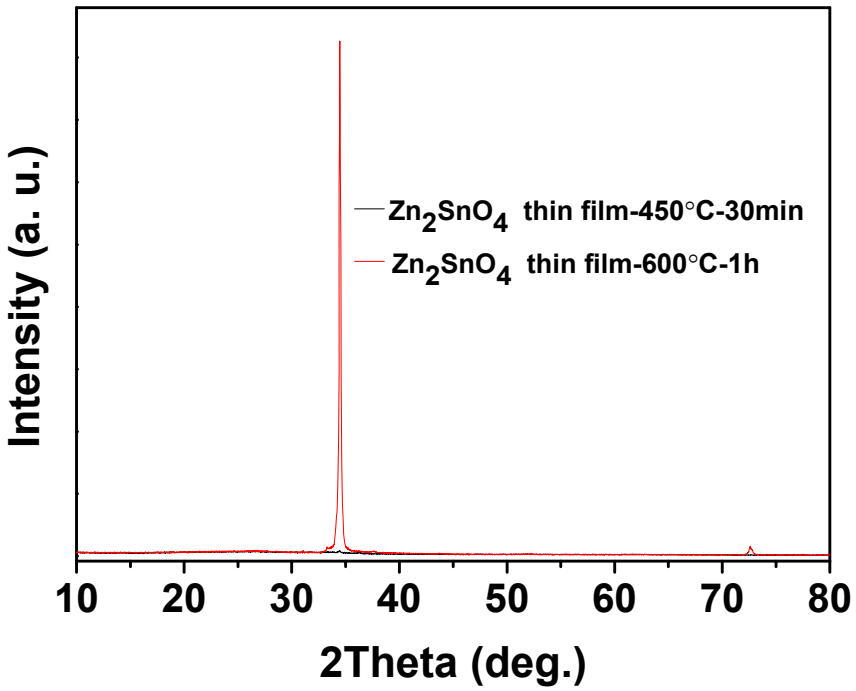

Fig. S3. XRD patterns of pristine Zn_2SnO_4 thin films (~1.8 μm) annealed at 450 and 600 ^oC, respectively.

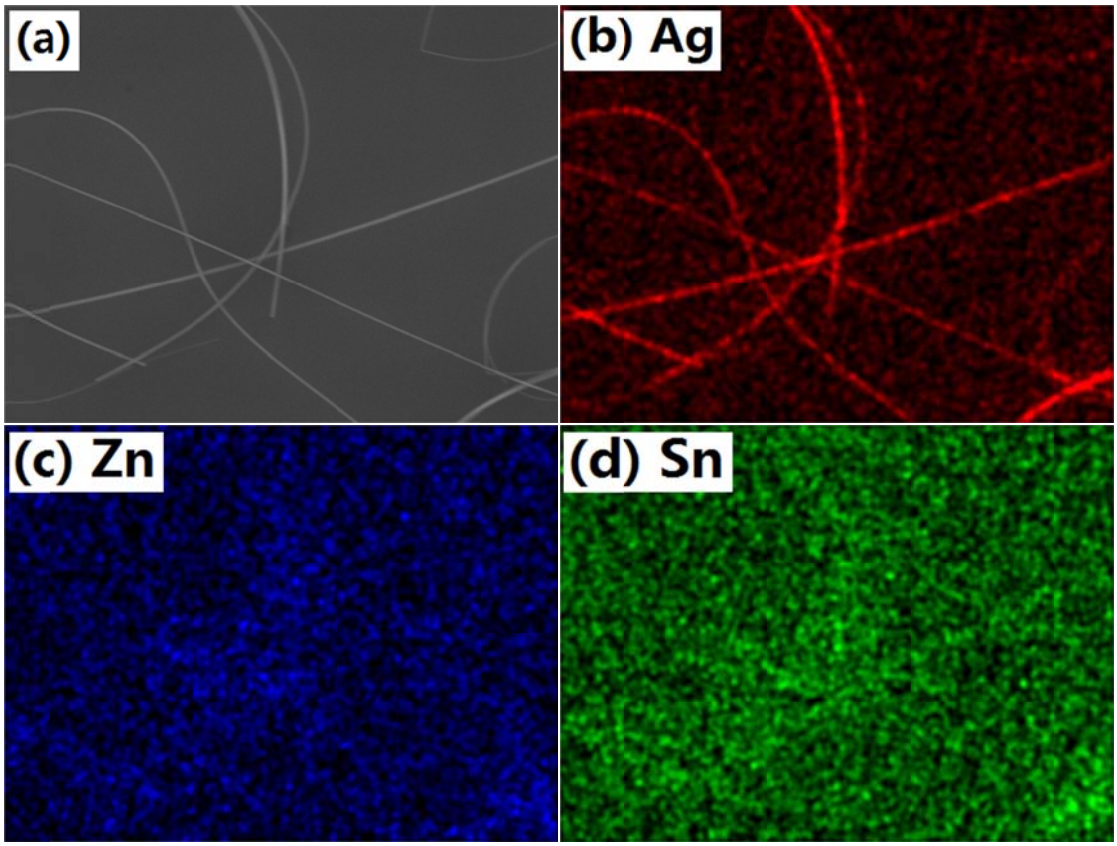

Fig. S4. SEM image (a) and corresponding elemental maps (b, c and d) of as-prepared AgNW/Zn_2SnO_4 composite thin film on silicon wafers.

Table S1. The relationships between the thickness of the Zn_2SnO_4 layer and the concentration of Zn_2SnO_4 precursor solution as well as the spin-coating rate.

Thickness of the Zn_2SnO_4 layer (nm)				
	1 mL ethanol	2.5 mL ethanol	5 mL ethanol	10 mL ethanol
2000 rpm, 10 s	855	335	156	56
2600 rpm,10 s	770	293	120	51
2600 rpm, 20 s	629	250	64	24